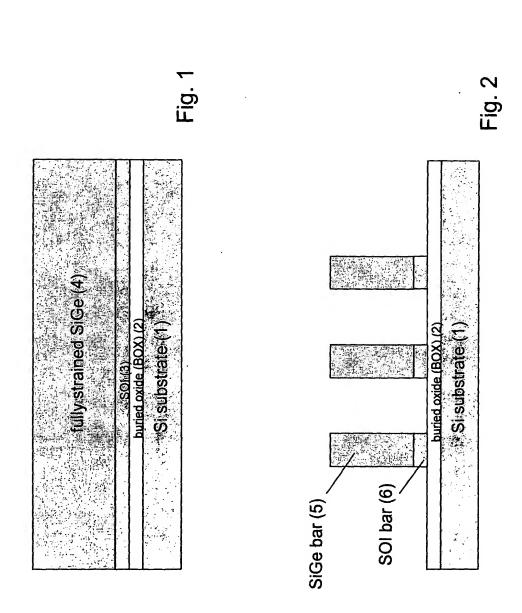
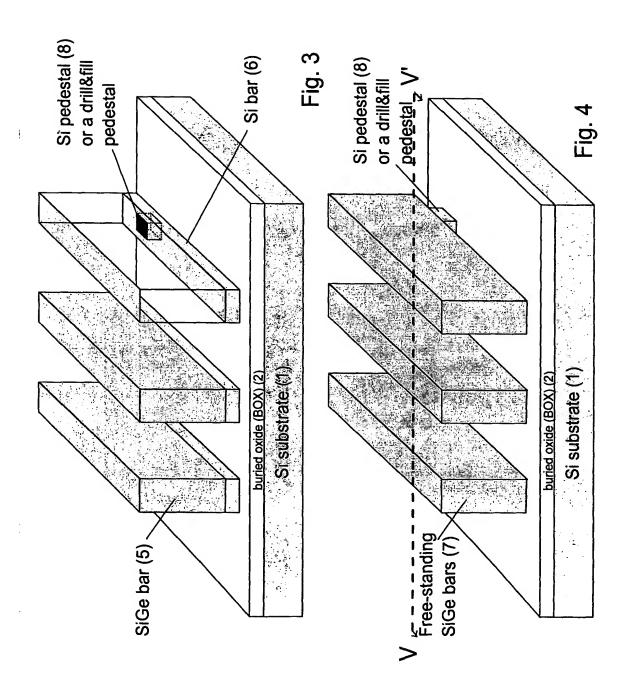
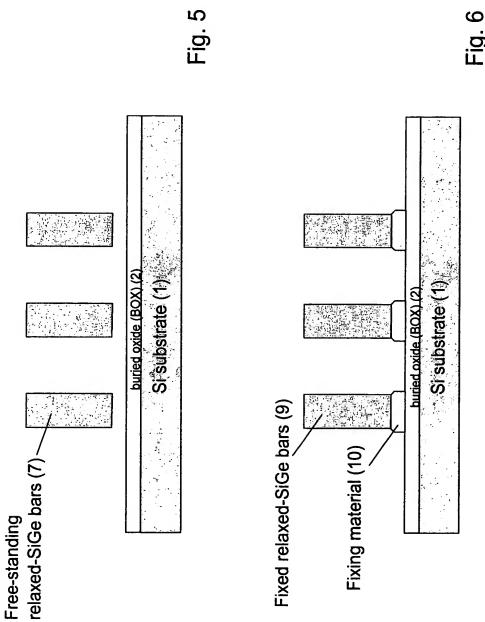
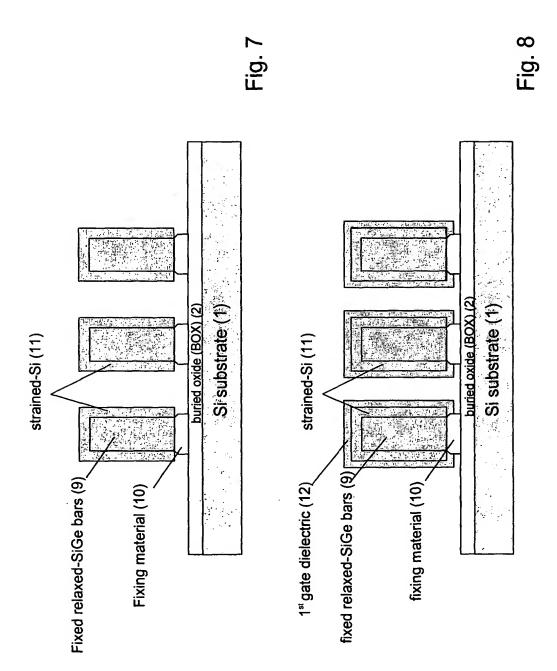
I/I3 Guy Cohen TAD YOR920030328USI



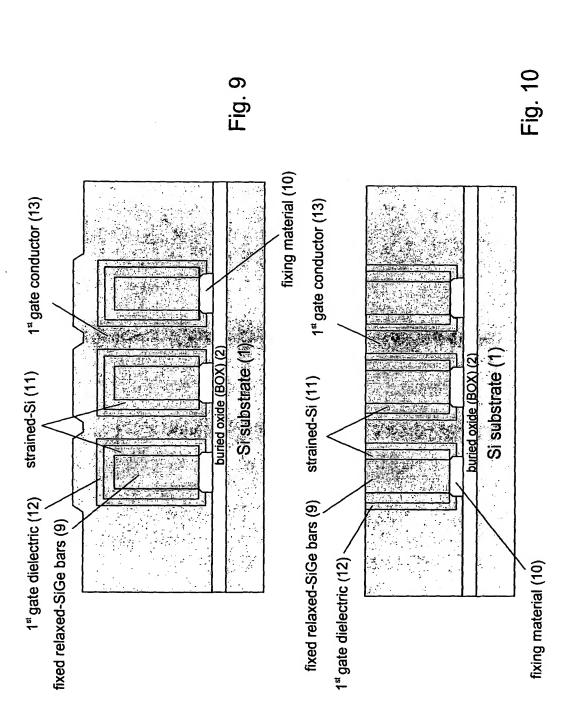
2/13 Guy Cohen YOR920030328US1

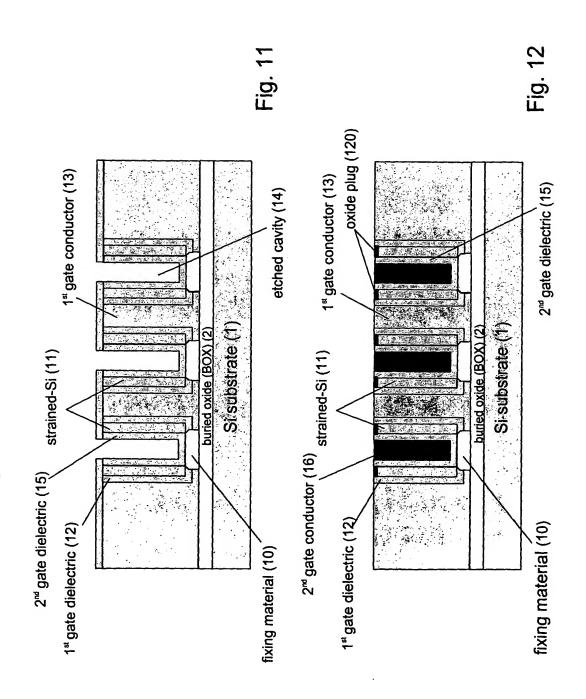


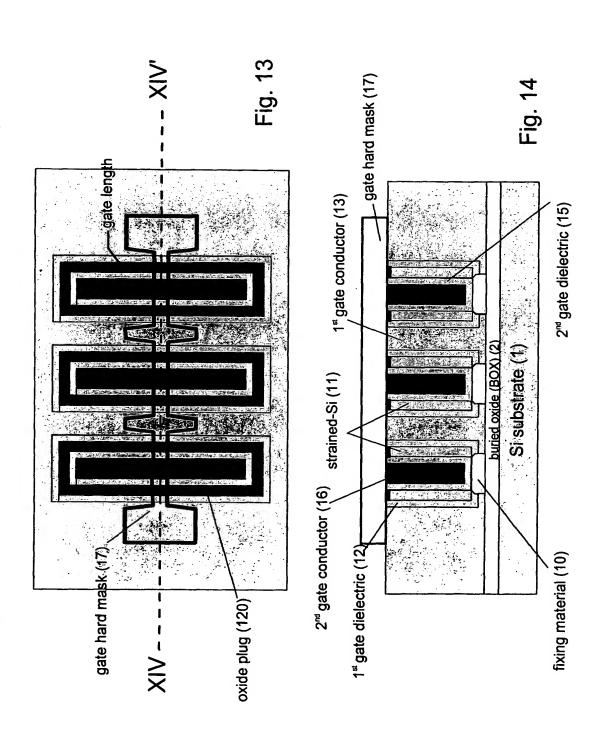




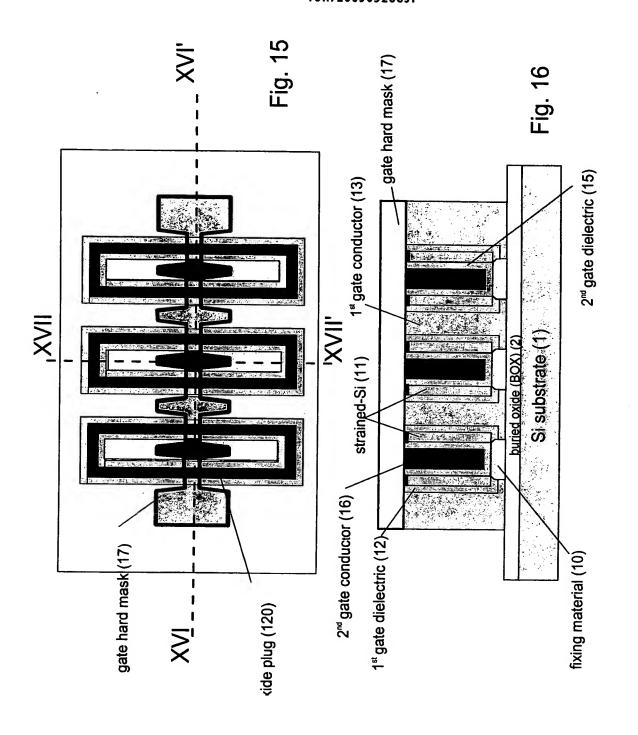
5/13 Guy Cohen YOR920030328USI



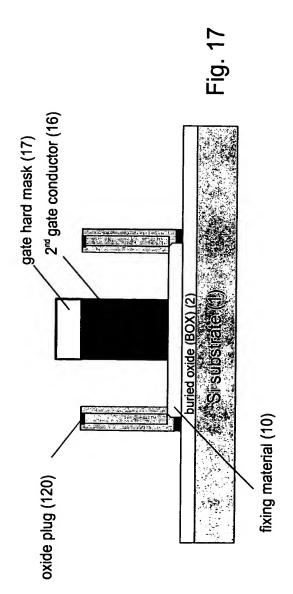




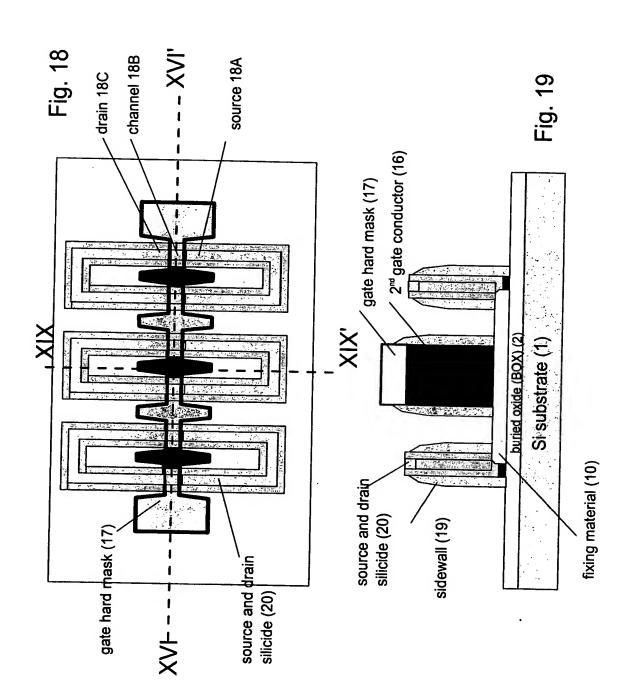
8/13 Guy Cohen YOR920030328USI

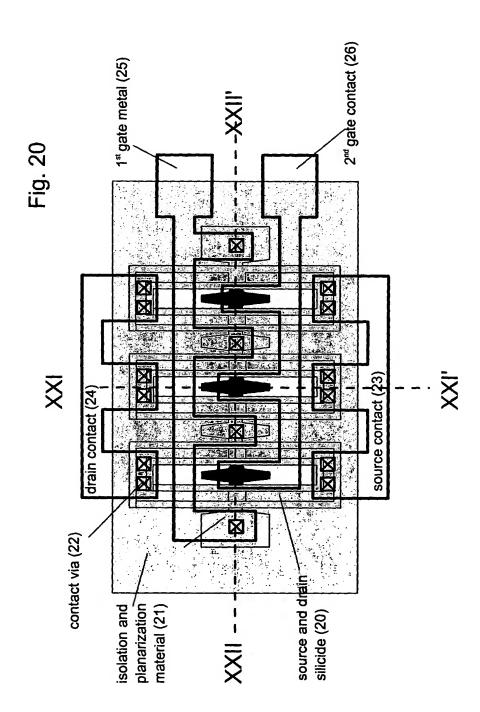


9/13 Guy Cohen YOR920030328US1

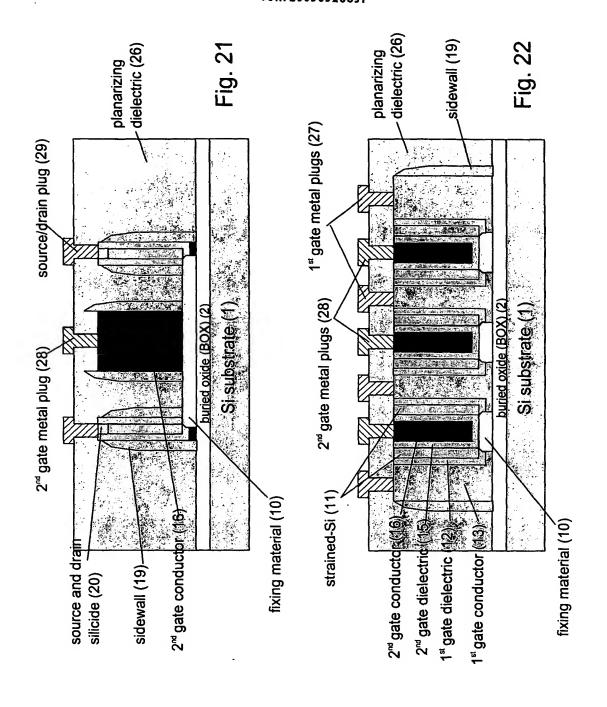


10/13 Guy Cohen YOR920030328US1





12/13 Guy Cohen YOR920030328US1



13/13 Guy Cohen YOR920030328US1

*** rielaxed semiconductor (242)

buried oxide (BOX) (241)

Si substrate (240)

strained-Si (252) relaxed semiconductor bars (251)

Fig. 24

Si substrate (240)

buried oxide (BOX